

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	3533	Carbon near5 barrier	US-PGPU B; USPAT; USOCR	OR	ON	2007/07/23 00:44
L2	1260	L1 and plasma	US-PGPU B; USPAT; USOCR	OR	ON	2007/07/23 00:45
L3	596	L2 and (resist photoresist PR)	US-PGPU B; USPAT; USOCR	OR	ON	2007/07/23 00:45
L4	557	L3 and (etch\$3 trim\$4 pattern\$3)	US-PGPU B; USPAT; USOCR	OR	ON	2007/07/23 00:46
L5	519	L4 and (insulat\$3 dielectric opaque)	US-PGPU B; USPAT; USOCR	OR	ON	2007/07/23 00:45
L6	2816	Carbon same barrier	FPRS; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2007/07/23 00:45
L7	344	L6 and plasma	FPRS; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2007/07/23 00:45
L8	26	L7 and (resist photoresist PR)	FPRS; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2007/07/23 00:45
L9	97	L7 and (insulat\$3 dielectric opaque)	FPRS; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2007/07/23 00:46

EAST Search History

L11	11	L8 and L9	FPRS; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2007/07/23 00:47
-----	----	-----------	--	----	----	---------------------

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	188759	(substrate wafer).clm.	US-PGPU B	OR	ON	2007/07/23 00:52
L2	27065	(resist PR photoresist).clm.	US-PGPU B	OR	ON	2007/07/23 00:52
L3	126320	(trimming etching pattern\$3).clm.	US-PGPU B	OR	ON	2007/07/23 00:53
L4	196	(carbon near5 barrier). clm.	US-PGPU B	OR	ON	2007/07/23 00:54
L5	9	1 and 2 and 3 and 4	US-PGPU B	OR	ON	2007/07/23 00:54